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Filed Via Express Mail  
Rec. No.: EM366875348US  
On: November 5, 1999  
By: *Linda H. Helling*  
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Attorney Docket No.:NEKW14.868

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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Inventor : KAICHIRO NAKANO, ET AL.  
Serial No. : 09/036,219  
Filed : March 6, 1998  
Title : **CHEMICALLY AMPLIFIED RESIST LARGE IN  
TRANSPARENCY AND SENSITIVITY TO EXPOSURE  
LIGHT LESS THAN 248 NANOMETER WAVELENGTH  
AND PROCESS OF FORMING MASK**  
Examiner : J. Chu  
Group Art Unit : 1752

November 5, 1999

Assistant Commissioner for Patents  
Washington, D.C. 20231

**AMENDMENT**

SIR:

In response to the Office Action dated August 5, 1999, the period for responding thereto having been set to expire on November 5, 1999, please amend the subject application as follows:

**IN THE CLAIMS**

Please cancel claims 1 and 5, without prejudice.

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